

FIG. 1A  
PRIOR ART

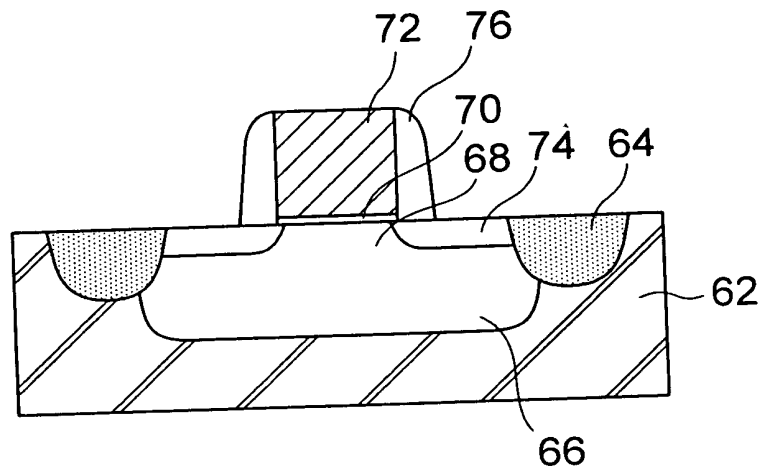
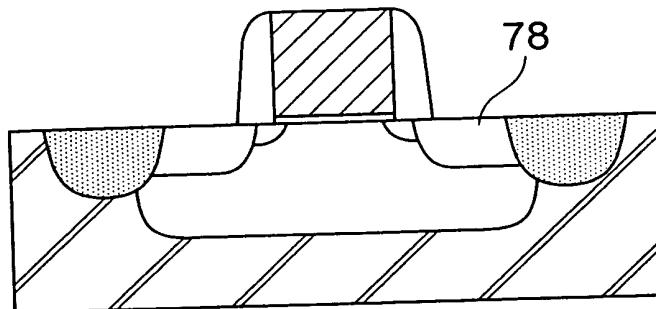
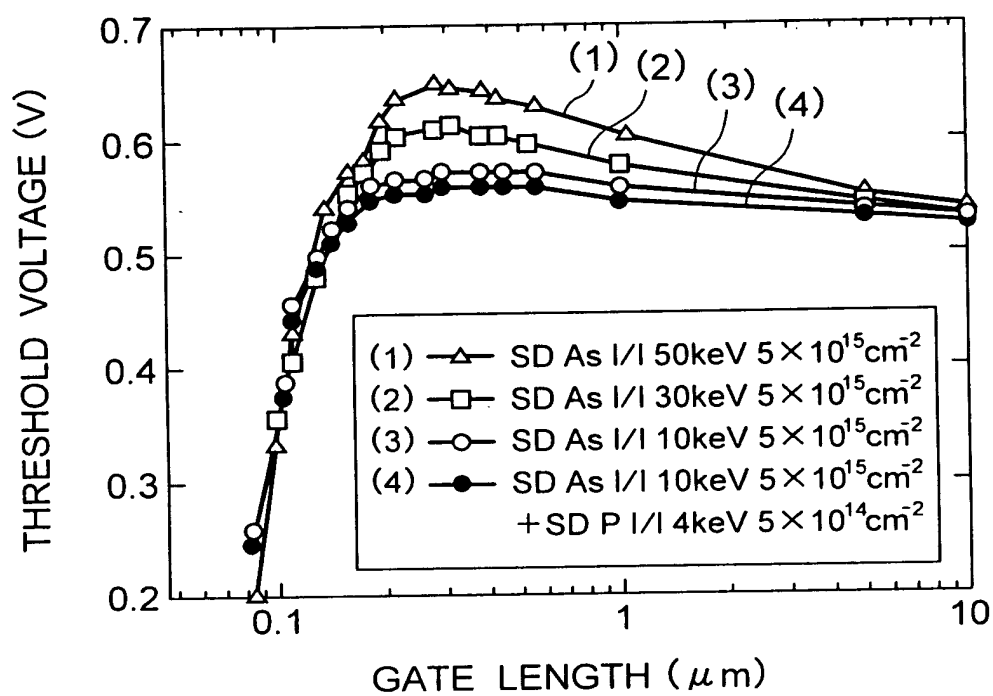


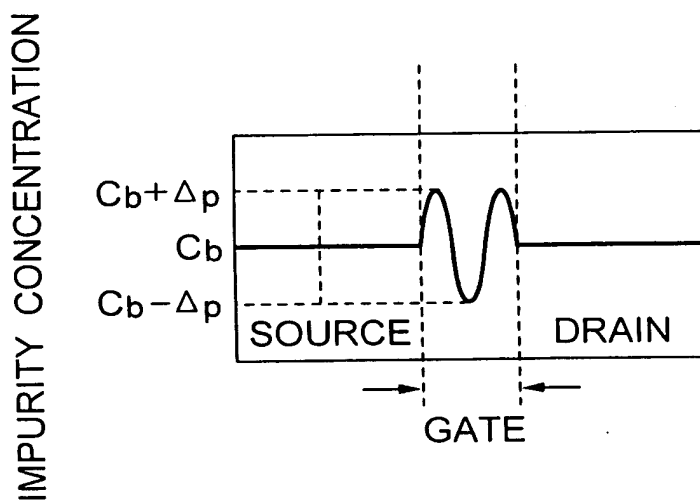
FIG. 1B  
PRIOR ART



# FIG. 2



# FIG. 3



# FIG. 4

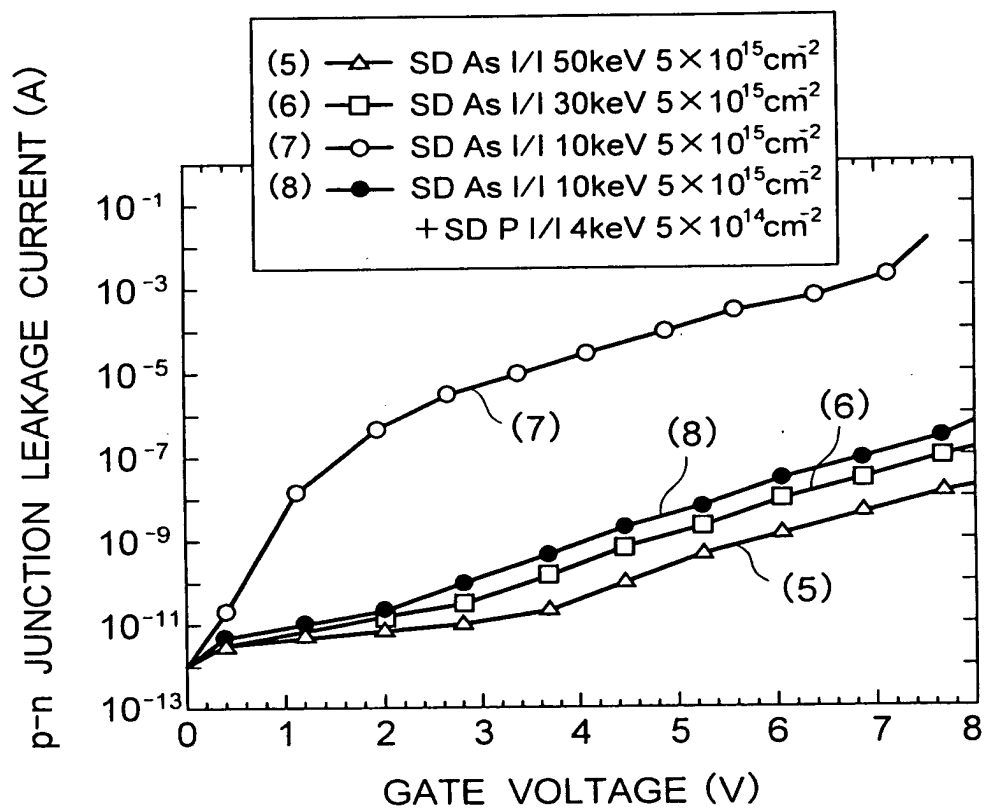


FIG. 5

INTERFACE BETWEEN AMORPHOUS SILICON  
REGION AND SILICON MONOCRYSTALLINE  
REGION WHEN As IS IMPLANTED AT  
10keV AND  $5 \times 10^{15} \text{cm}^{-2}$

INTERFACE BETWEEN AMORPHOUS SILICON  
REGION AND SILICON MONOCRYSTALLINE  
REGION WHEN As IS IMPLANTED AT  
50keV AND  $5 \times 10^{15} \text{cm}^{-2}$

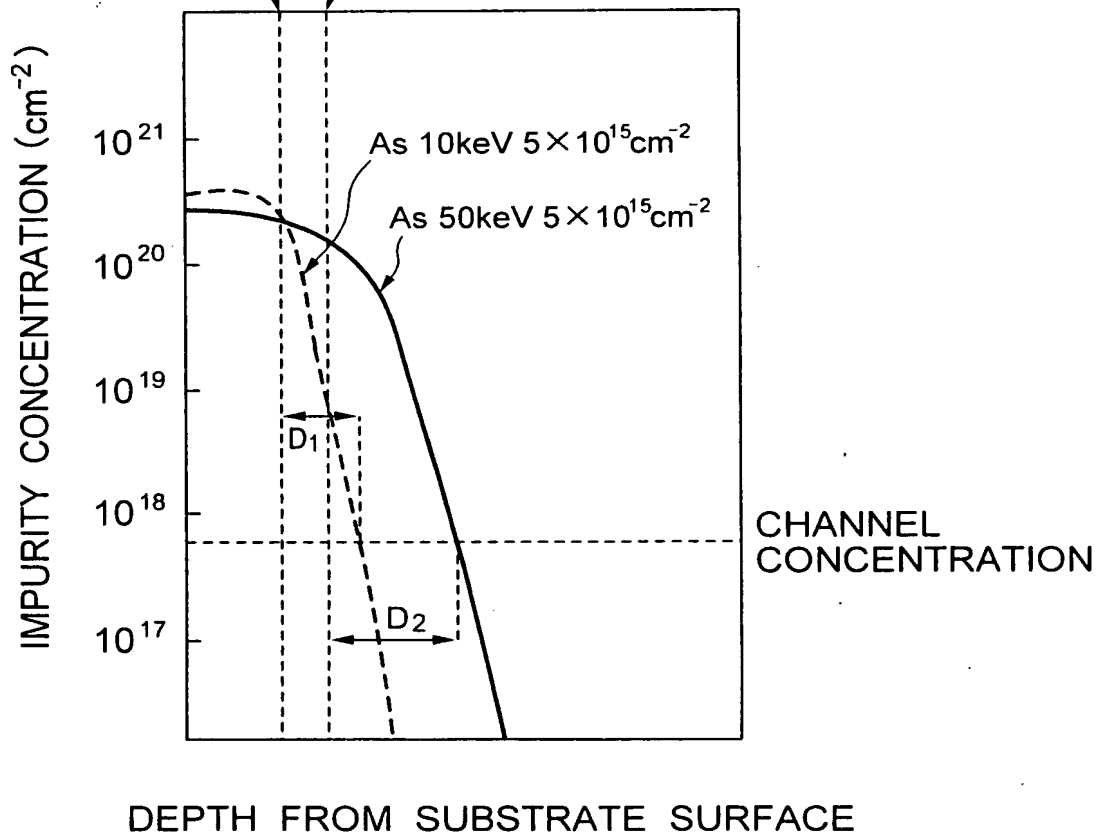
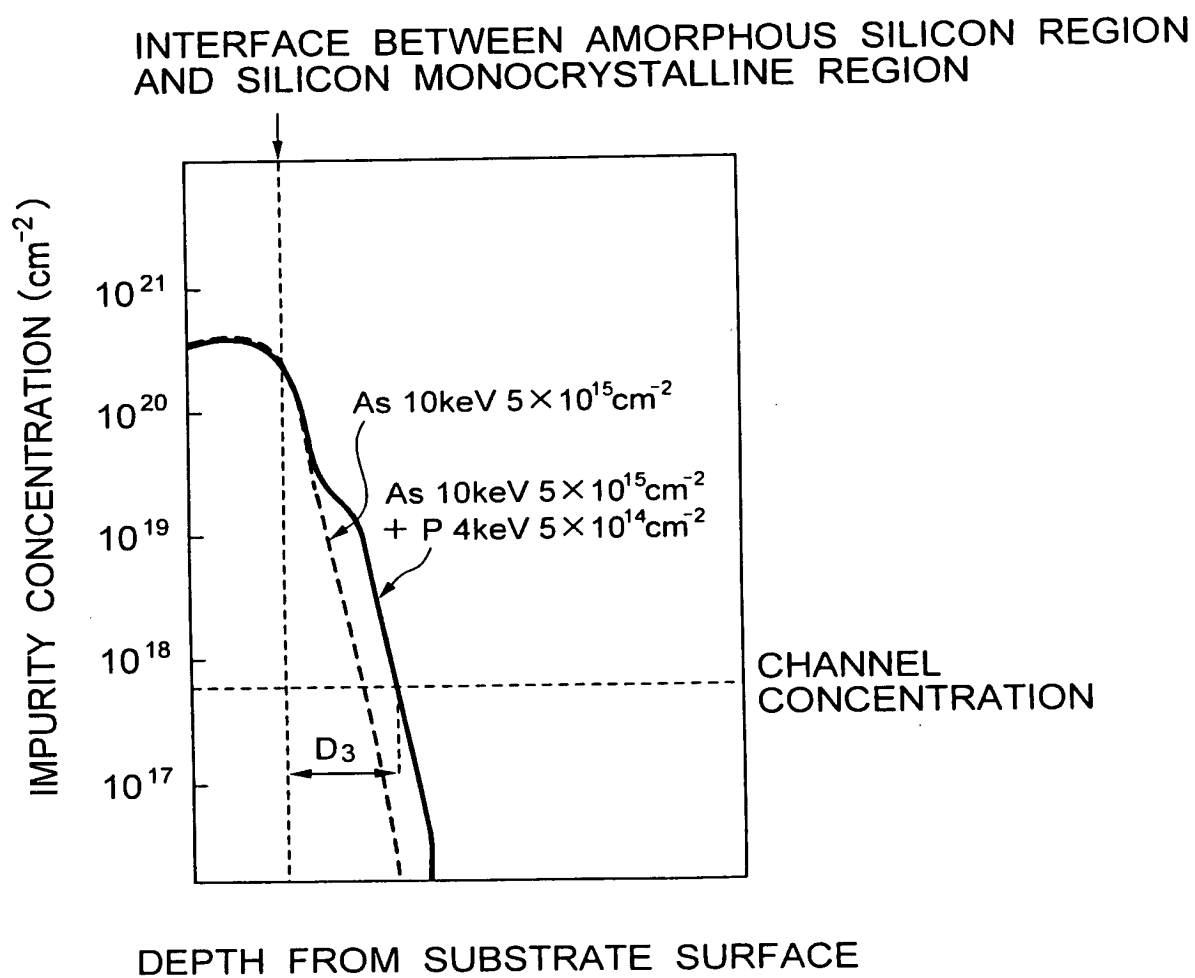
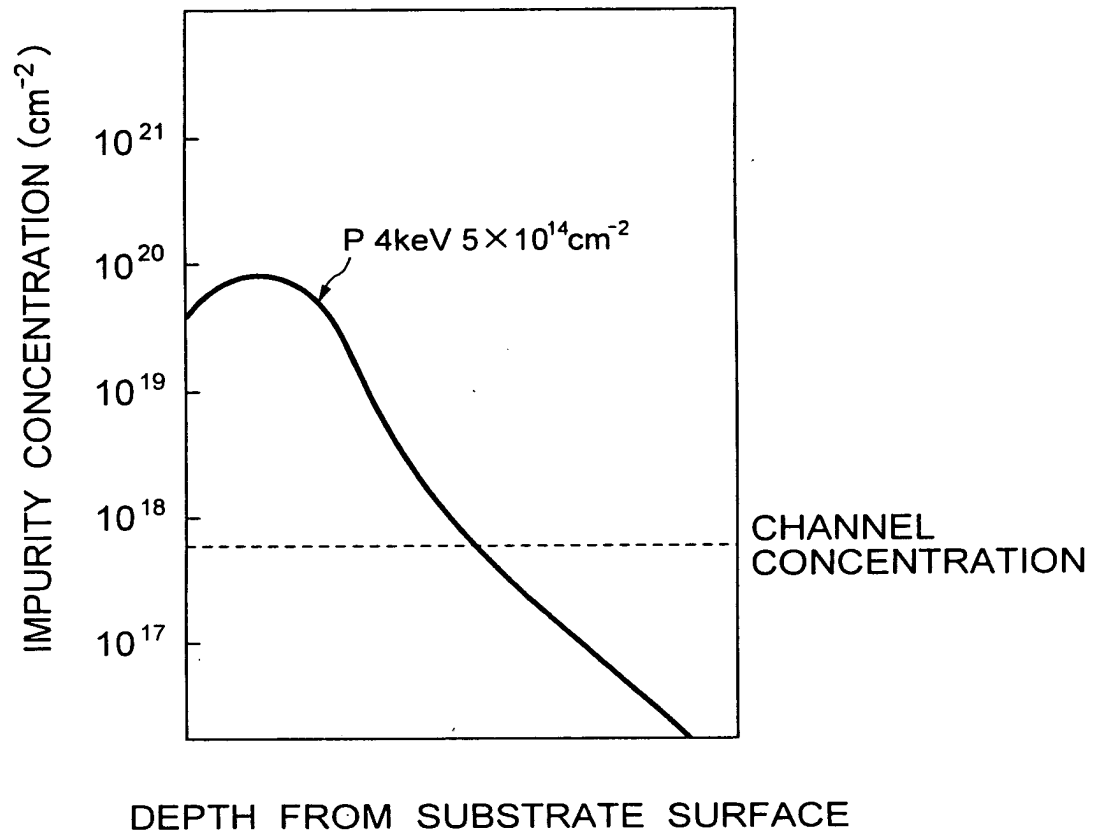


FIG. 6



# FIG. 7



# FIG. 8

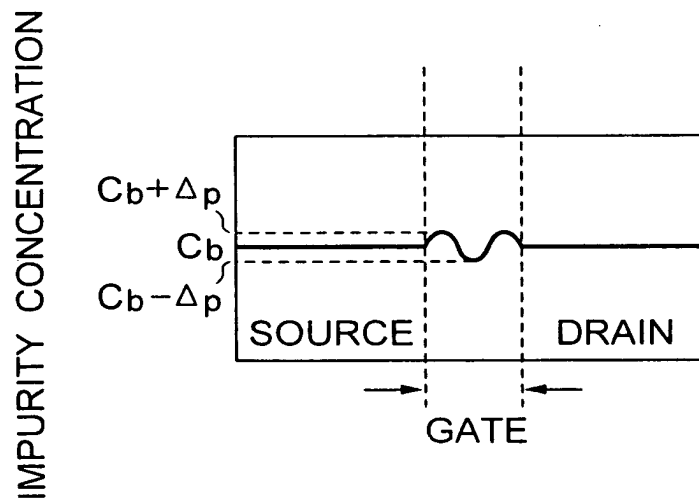
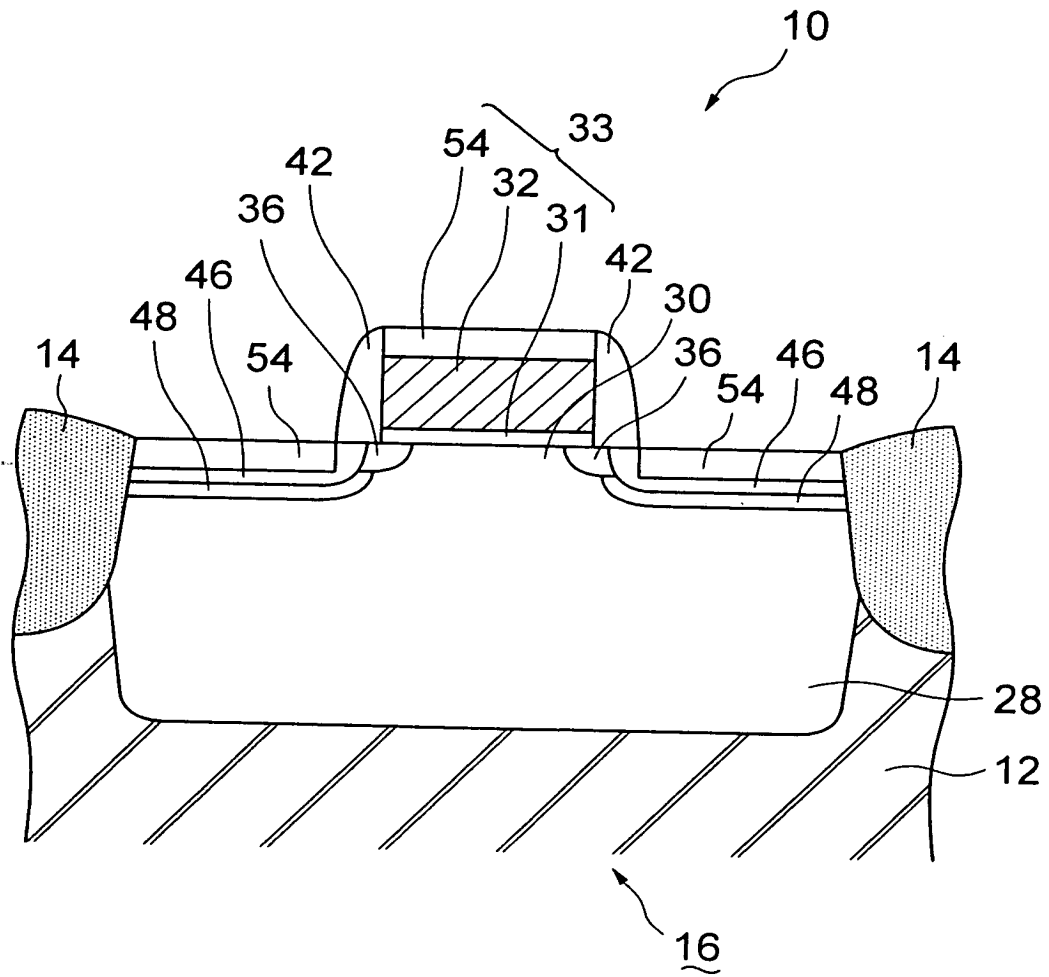
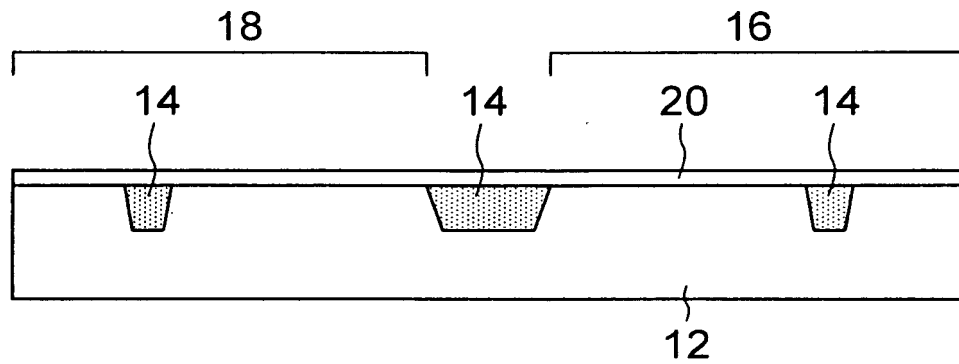


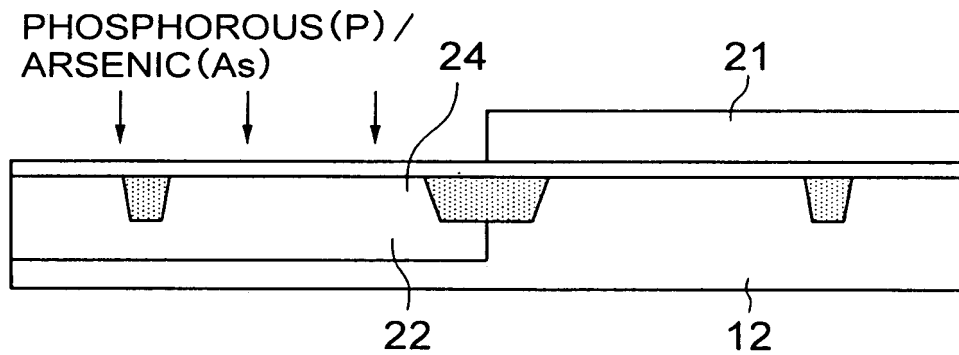
FIG.9



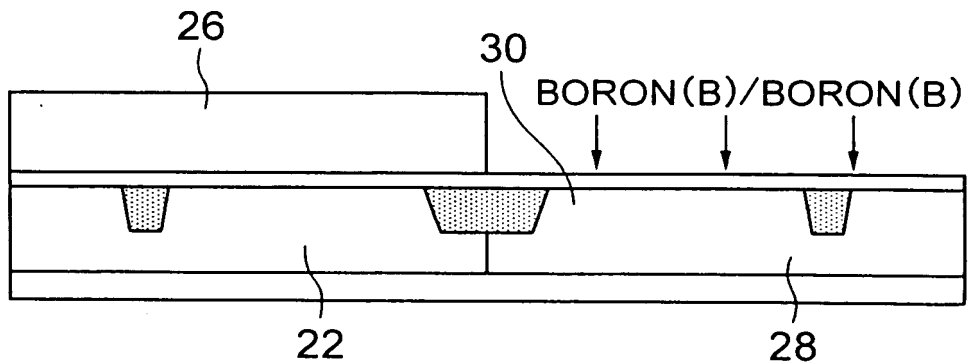
# FIG.10A



# FIG.10B

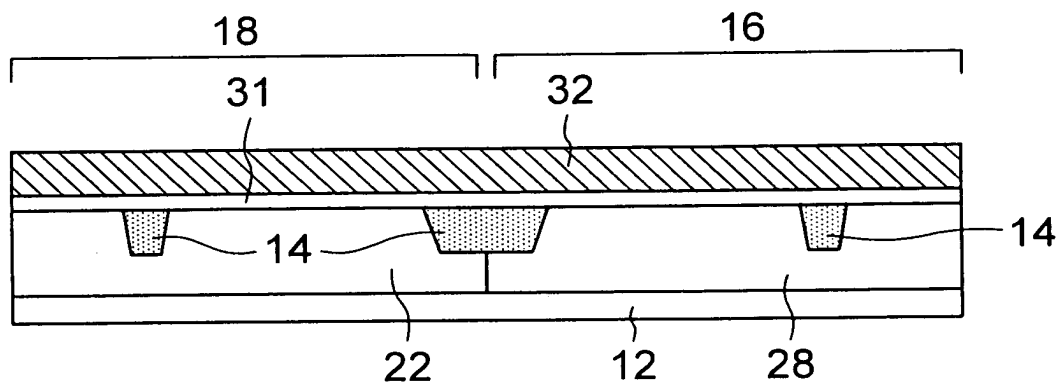


# FIG.10C

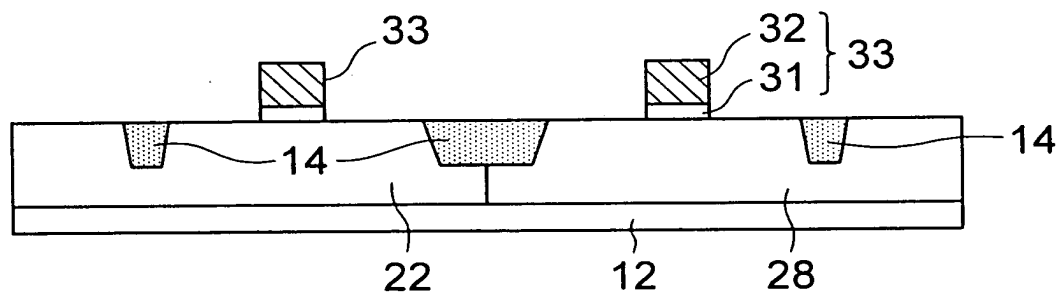




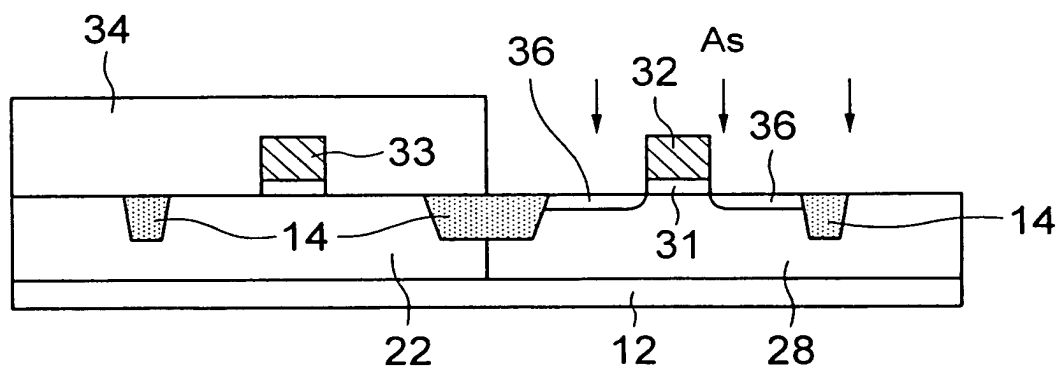
# FIG.10D

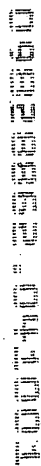


# FIG.10E



# FIG.10F



[illegible]

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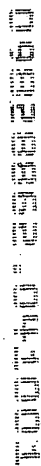
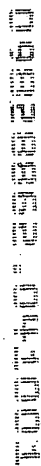
[illegible]

FIG.10J

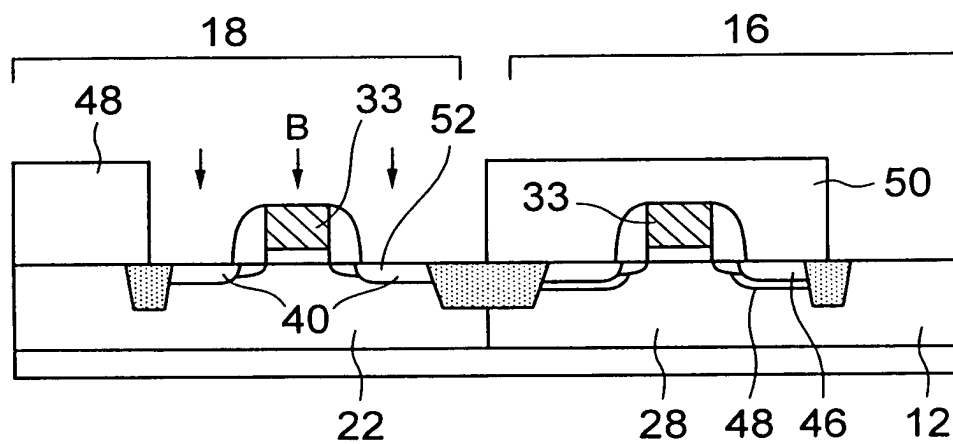


FIG.10K

